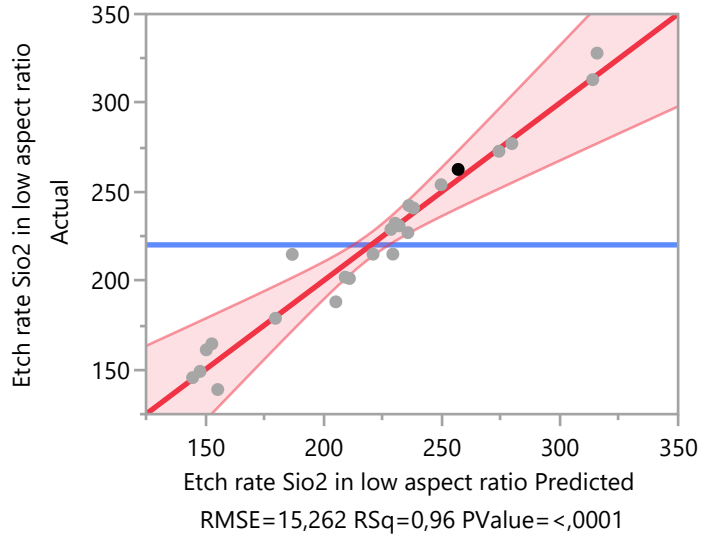


Fit Group

Response Etch rate Sio2 in low aspect ratio

Actual by Predicted Plot



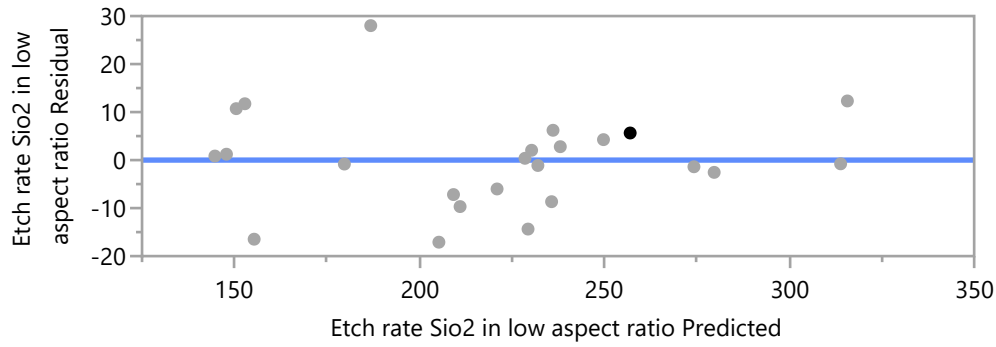
Effect Summary

Source	LogWorth	PValue
Platen power(200,300)	6,244	0,00000
Coil power*Total flow	3,208	0,00062
Total flow(100,500)	3,198	0,00063 ^
Total flow*He/C4F8	2,823	0,00150
He/C4F8(5,30)	2,760	0,00174 ^
Platen power*Total flow	2,696	0,00201
Coil power*Coil power	1,850	0,01412
Platen power*He/C4F8	1,559	0,02764
Coil power*C4F8/H2	1,406	0,03926
Platen power*C4F8/H2	1,343	0,04545
Coil power*He/C4F8	1,339	0,04576
Coil power(2500,4000)	0,649	0,22458 ^
C4F8/H2(1,3)	0,387	0,40985 ^

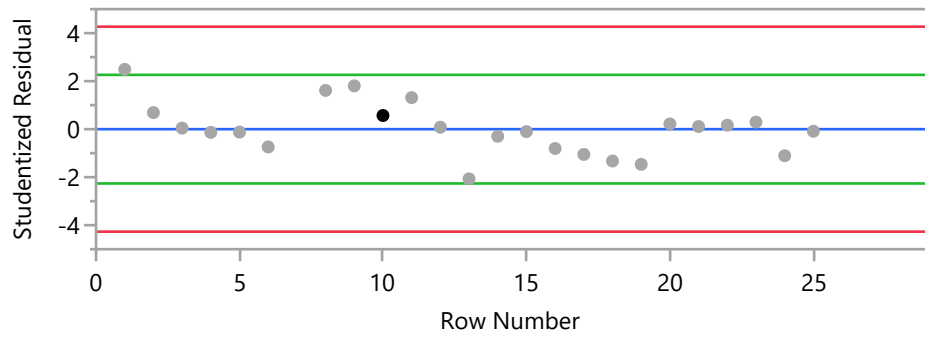
Fit Group

Response Etch rate Sio2 in low aspect ratio

Residual by Predicted Plot



Studentized Residuals

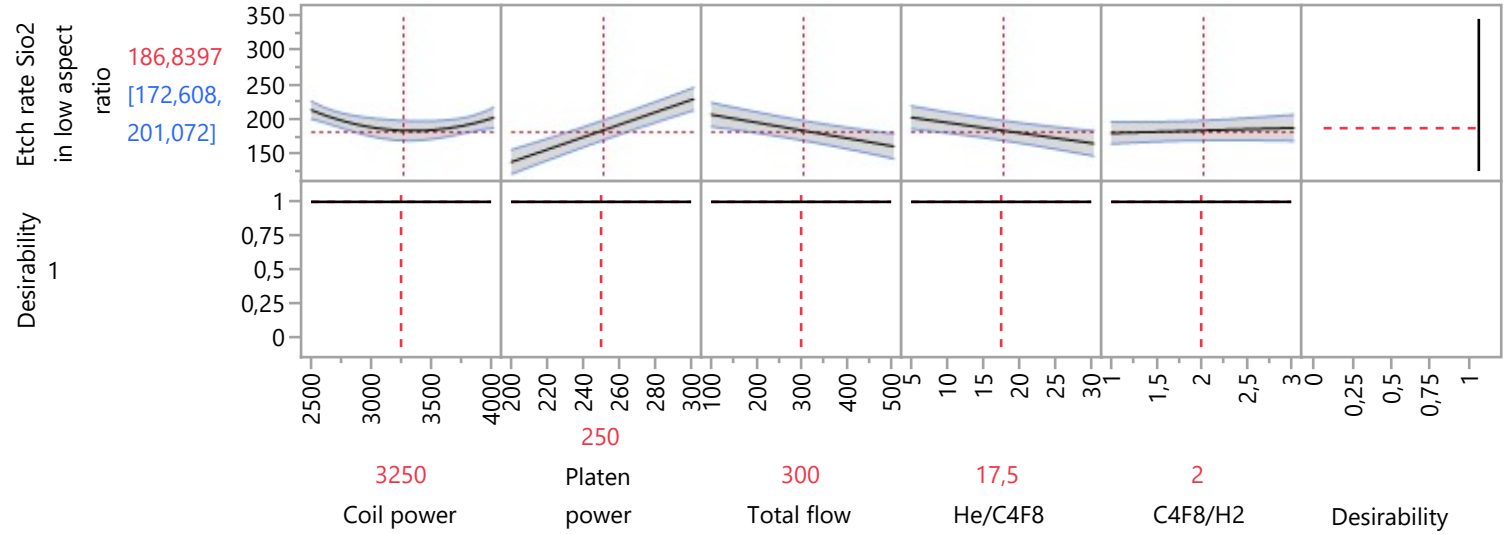


Externally studentized residuals with 95% simultaneous limits (Bonferroni) in red, individual limits in green.

Fit Group

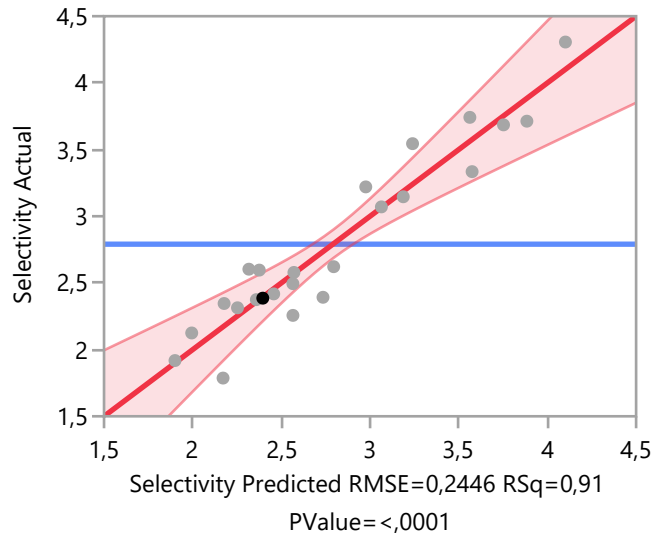
Response Etch rate Sio2 in low aspect ratio

Prediction Profiler



Response Selectivity

Actual by Predicted Plot



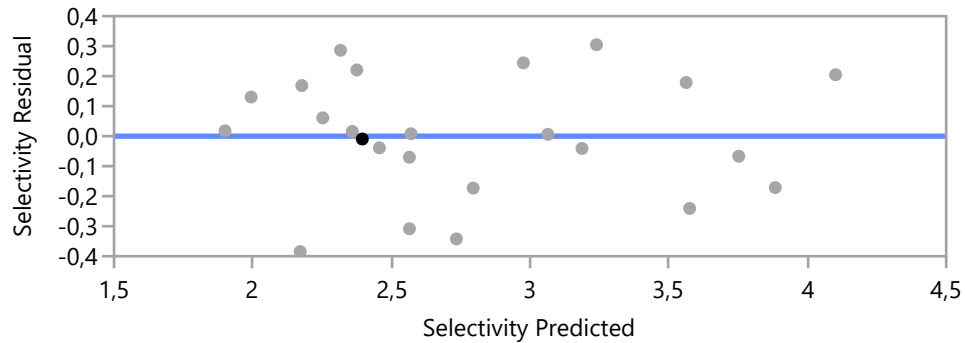
Fit Group

Response Selectivity

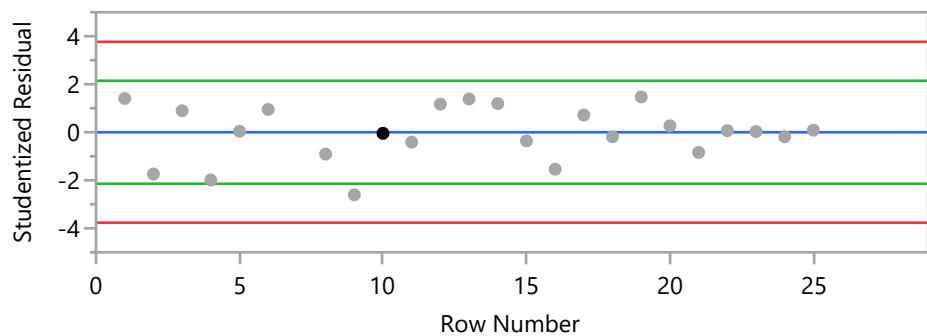
Effect Summary

Source	LogWorth	PValue
Platen power(200,300)	5,071	0,00001
Coil power(2500,4000)	4,687	0,00002
Total flow*He/C4F8	2,635	0,00232
Total flow*Total flow	2,493	0,00321
C4F8/H2(1,3)	2,136	0,00732
Coil power*Platen power	1,611	0,02449
He/C4F8(5,30)	0,404	0,39453 ^
Total flow(100,500)	0,289	0,51400 ^

Residual by Predicted Plot



Studentized Residuals



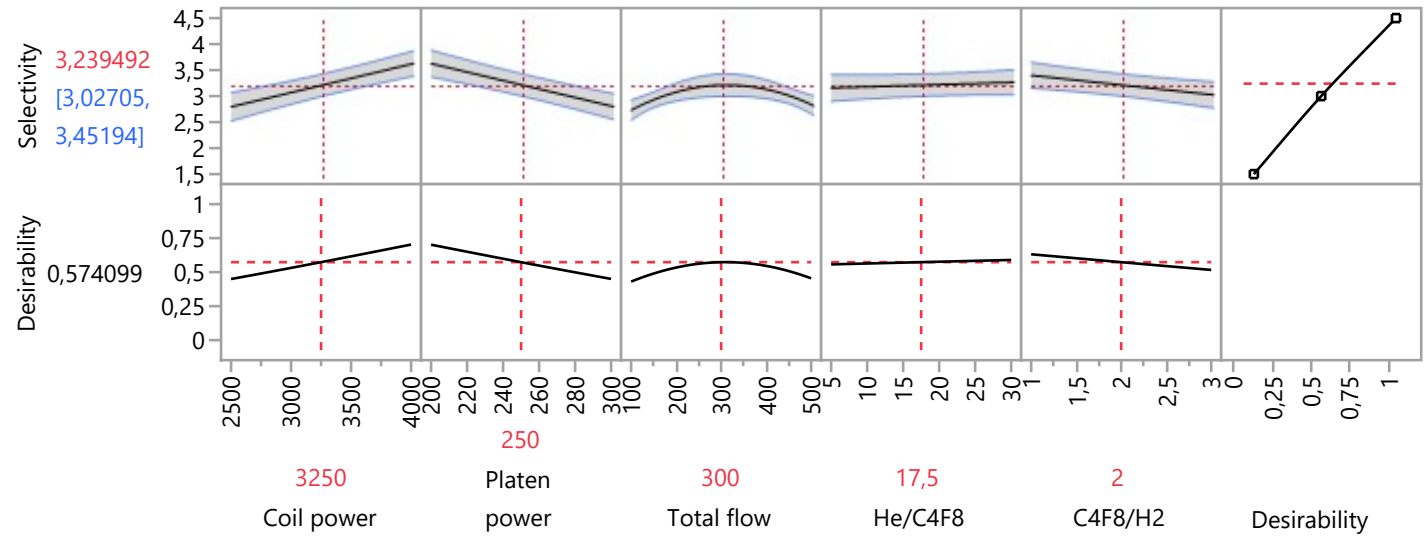
Fit Group

Response Selectivity

Studentized Residuals

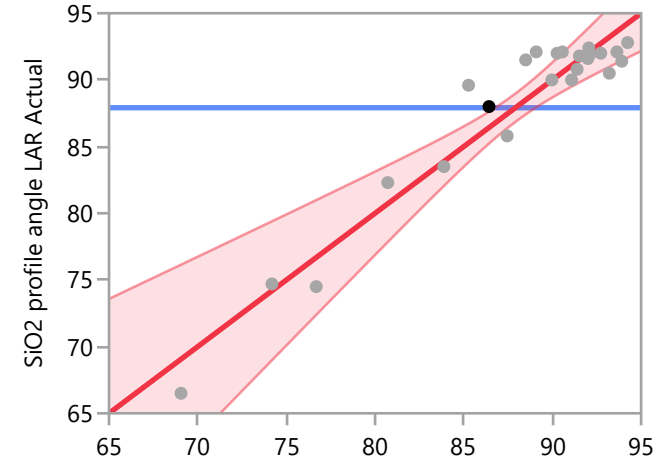
Externally studentized residuals with 95% simultaneous limits (Bonferroni) in red, individual limits in green.

Prediction Profiler



Response SiO2 profile angle LAR

Actual by Predicted Plot



Fit Group

Response SiO2 profile angle LAR

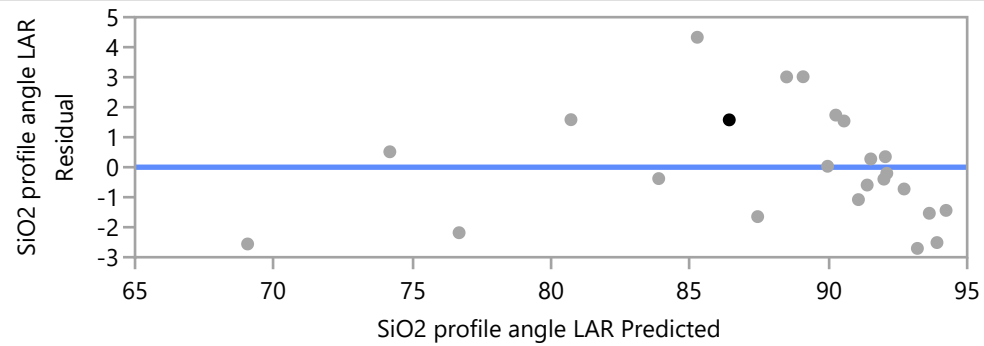
Actual by Predicted Plot

$R^2=0,921$ F value=5,0001

Effect Summary

Source	LogWorth	PValue
He/C4F8(5,30)	5,699	0,00000
Total flow(100,500)	4,458	0,00003
Total flow*He/C4F8	3,608	0,00025
Platen power*Platen power	2,394	0,00404
Coil power*C4F8/H2	1,881	0,01315
Platen power(200,300)	1,332	0,04657 ^
Coil power*He/C4F8	1,302	0,04988
Coil power(2500,4000)	0,553	0,27965 ^
C4F8/H2(1,3)	0,151	0,70677 ^

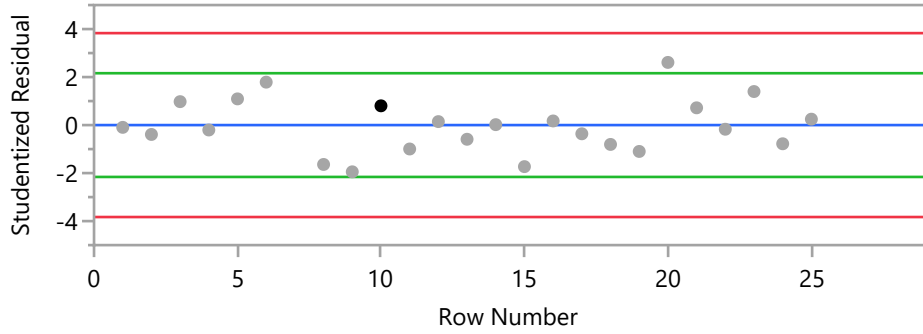
Residual by Predicted Plot



Fit Group

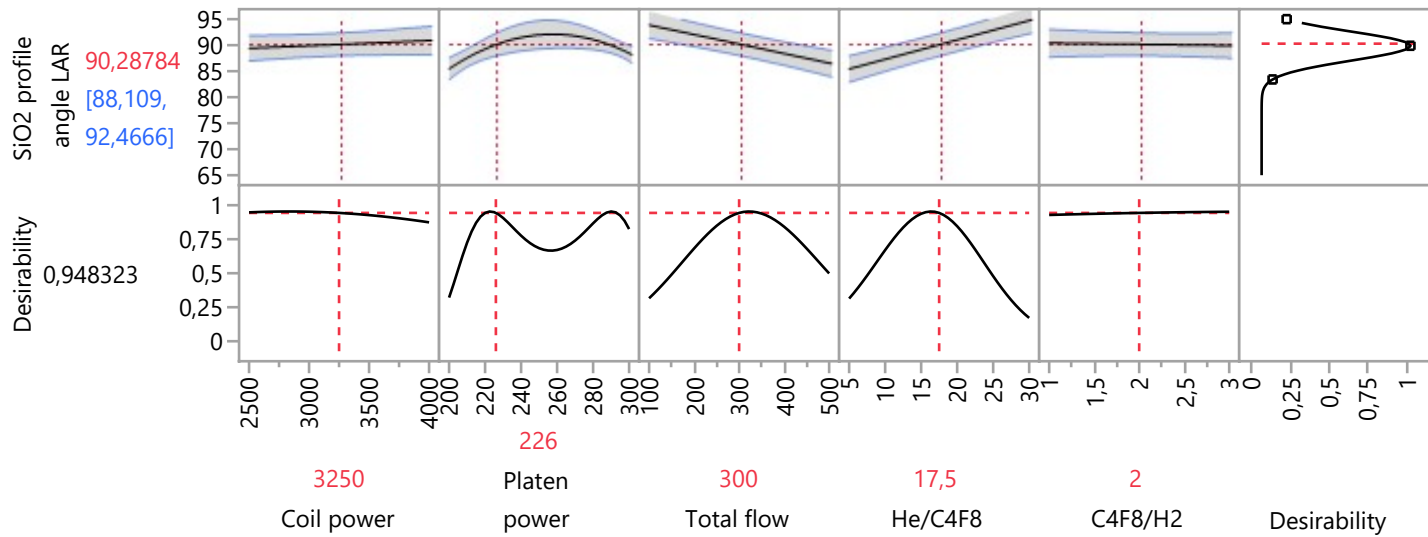
Response SiO2 profile angle LAR

Studentized Residuals



Externally studentized residuals with 95% simultaneous limits (Bonferroni) in red, individual limits in green.

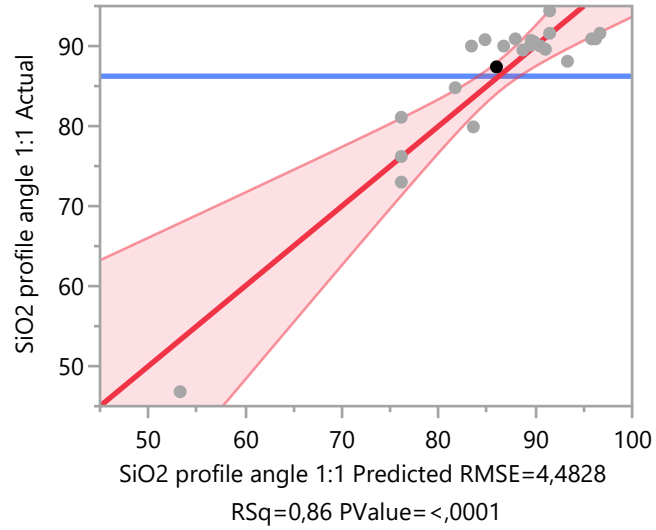
Prediction Profiler



Fit Group

Response SiO2 profile angle 1:1

Actual by Predicted Plot



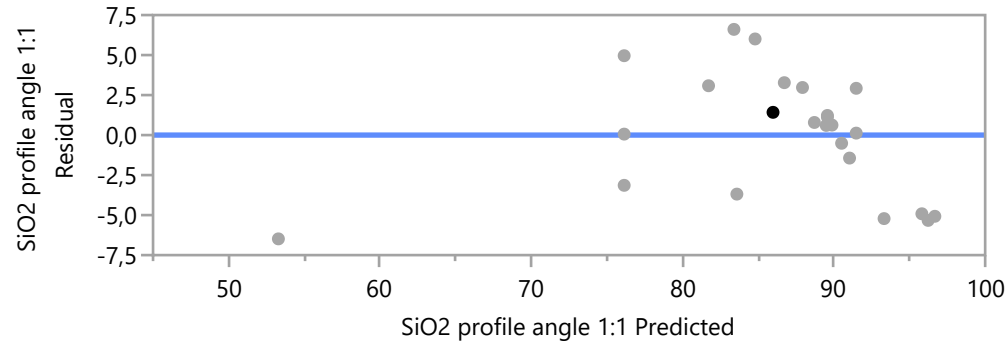
Effect Summary

Source	LogWorth		PValue
He/C4F8(5,30)	5,407		0,00000
Total flow(100,500)	4,089		0,00008
Total flow*He/C4F8	3,086		0,00082
Platen power(200,300)	2,439		0,00364
Platen power*Total flow	2,259		0,00551
Platen power*He/C4F8	1,831		0,01476
Platen power*Platen power	1,358		0,04389

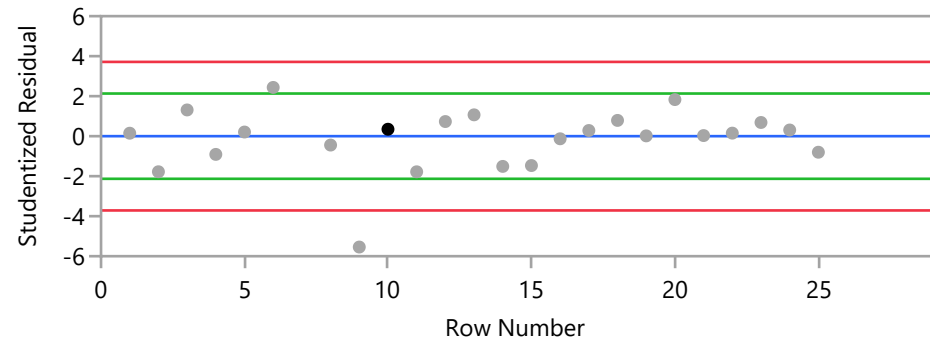
Fit Group

Response SiO2 profile angle 1:1

Residual by Predicted Plot



Studentized Residuals

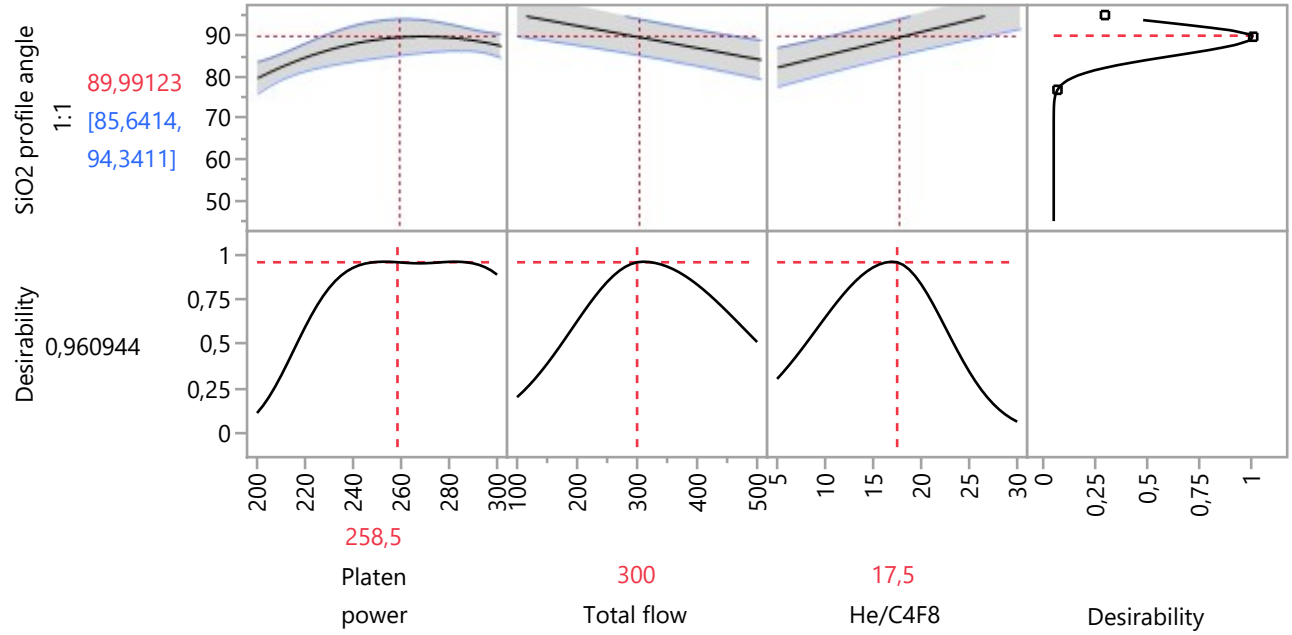


Externally studentized residuals with 95% simultaneous limits (Bonferroni) in red, individual limits in green.

Fit Group

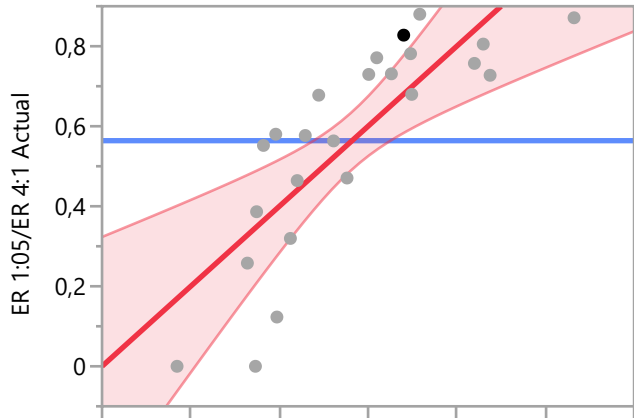
Response SiO2 profile angle 1:1

Prediction Profiler



Response ER 1:05/ER 4:1

Actual by Predicted Plot



Fit Group

Response ER 1:05/ER 4:1

Actual by Predicted Plot

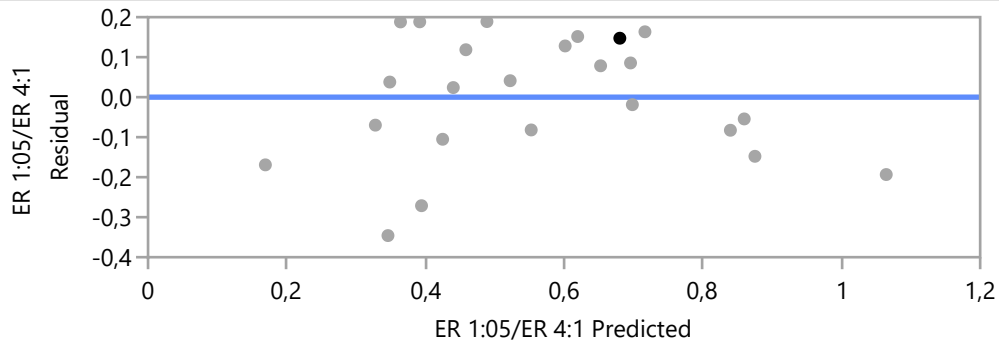
ER 1:05/ER 4:1 Predicted RMSE=0,1685 RSq=0,66

PValue=0,0002

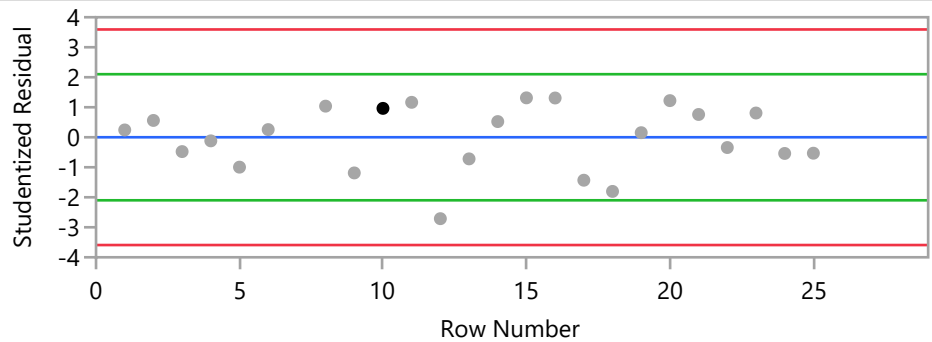
Effect Summary

Source	LogWorth		PValue
Platen power(200,300)	3,773		0,00017
Total flow(100,500)	2,582		0,00262
He/C4F8(5,30)	2,239		0,00577
Coil power(2500,4000)	1,750		0,01780

Residual by Predicted Plot



Studentized Residuals

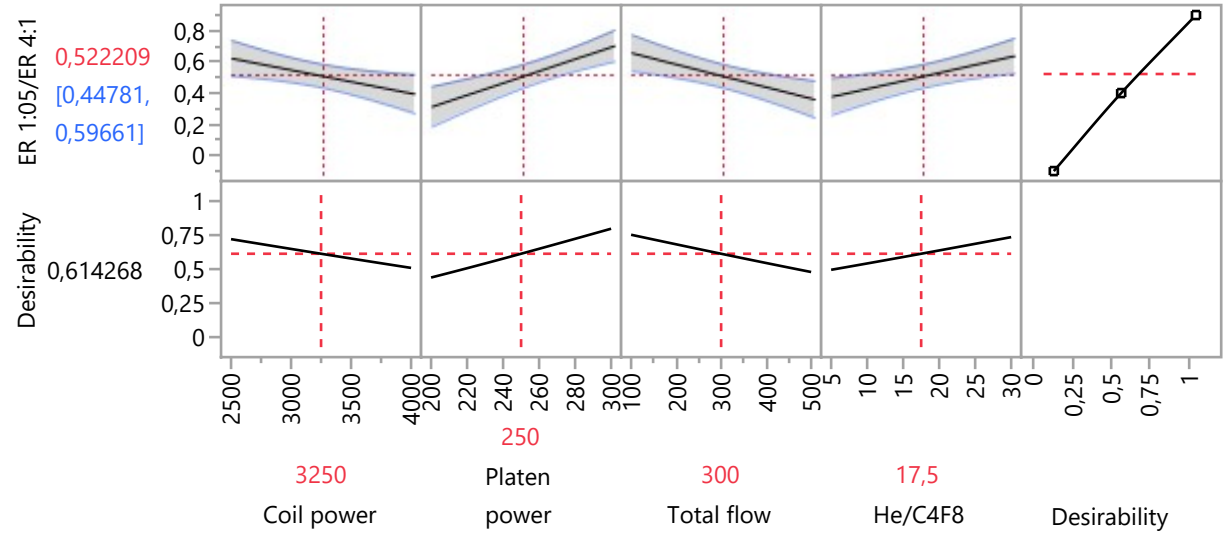


Externally studentized residuals with 95% simultaneous limits (Bonferroni) in red, individual limits in green.

Fit Group

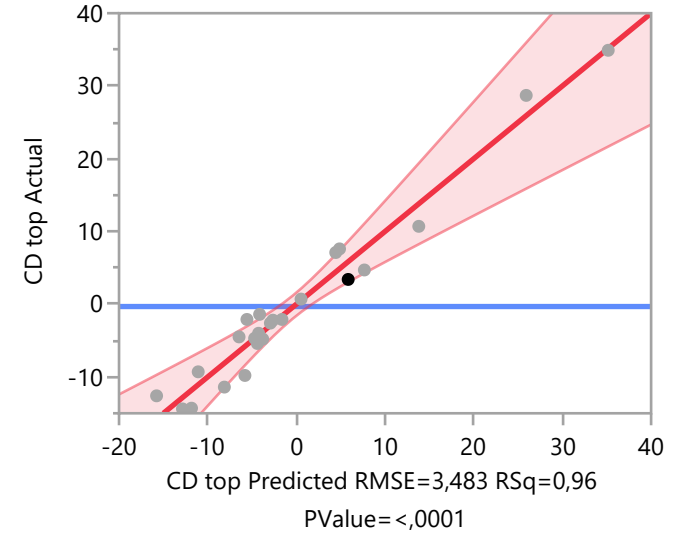
Response ER 1:05/ER 4:1

Prediction Profiler



Response CD top

Actual by Predicted Plot



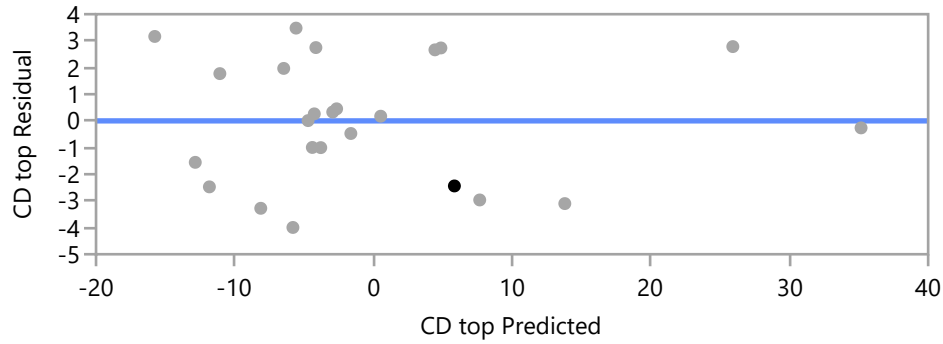
Fit Group

Response CD top

Effect Summary

Source	LogWorth	PValue
He/C4F8(5,30)	4,630	0,00002
Total flow*He/C4F8	4,570	0,00003
Total flow(100,500)	3,156	0,00070 ^
Coil power(2500,4000)	2,880	0,00132
Platen power*He/C4F8	2,560	0,00276
Total flow*C4F8/H2	2,170	0,00676
Platen power(200,300)	2,136	0,00730 ^
Coil power*Platen power	1,840	0,01446
Platen power*C4F8/H2	1,809	0,01554
Coil power*Coil power	1,749	0,01783
Platen power*Platen power	1,728	0,01870
He/C4F8*He/C4F8	1,578	0,02642
C4F8/H2(1,3)	0,018	0,95851 ^

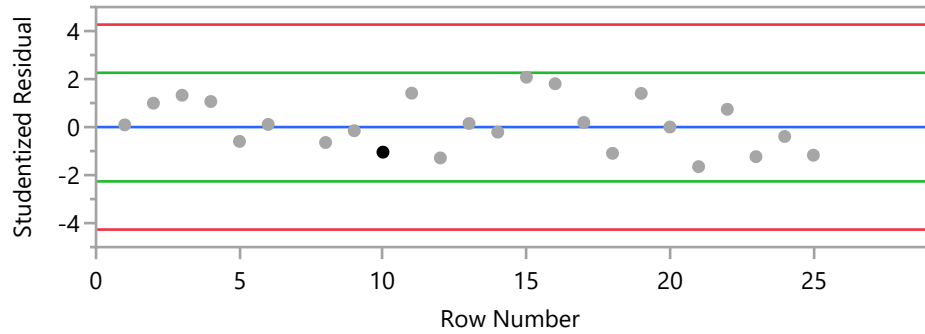
Residual by Predicted Plot



Fit Group

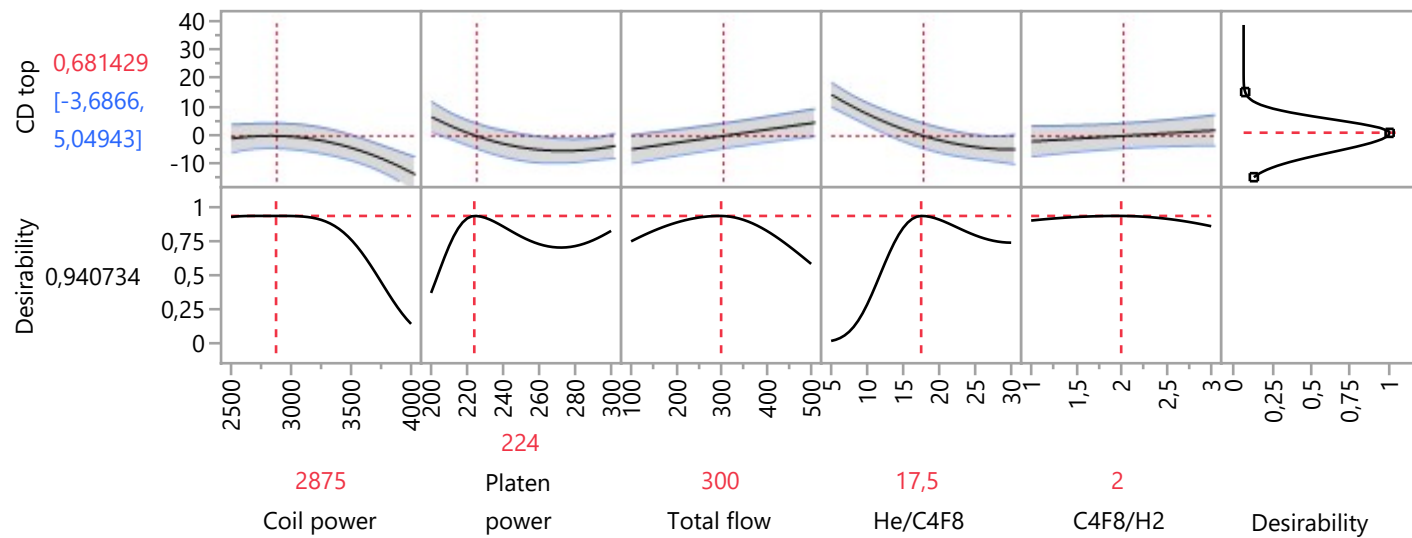
Response CD top

Studentized Residuals



Externally studentized residuals with 95% simultaneous limits (Bonferroni) in red, individual limits in green.

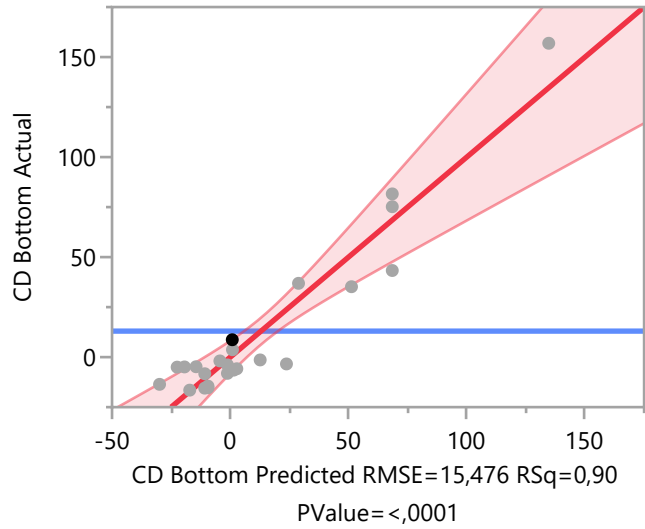
Prediction Profiler



Fit Group

Response CD Bottom

Actual by Predicted Plot



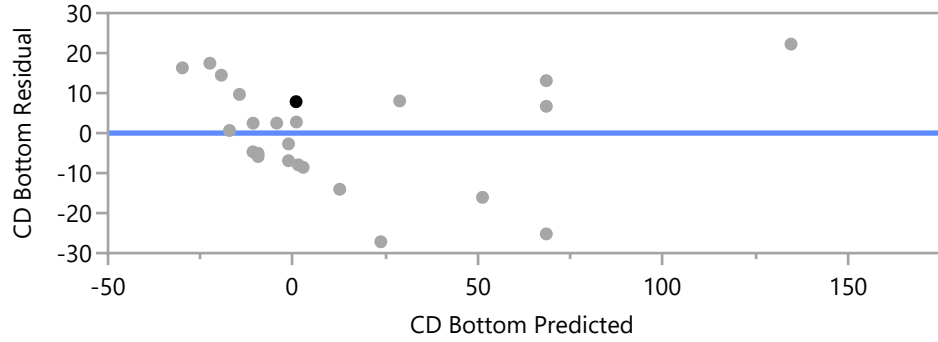
Effect Summary

Source	LogWorth	PValue
He/C4F8(5,30)	6,351	0,00000
Total flow*He/C4F8	5,018	0,00001
Total flow(100,500)	4,433	0,00004 ^
Platen power(200,300)	2,213	0,00613
He/C4F8*He/C4F8	1,617	0,02418
Platen power*Total flow	1,523	0,02997
Platen power*He/C4F8	1,497	0,03186

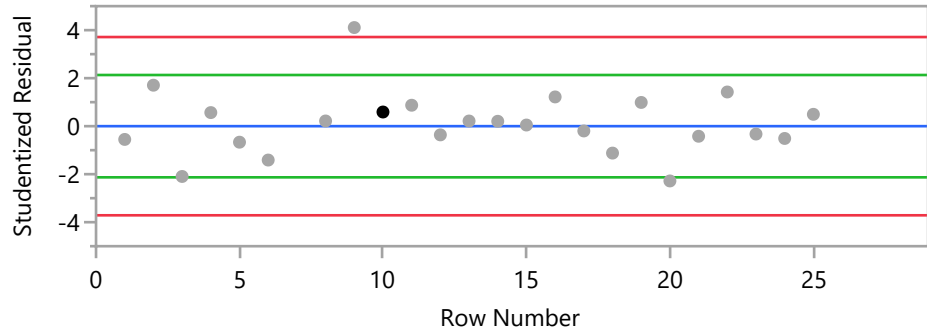
Fit Group

Response CD Bottom

Residual by Predicted Plot



Studentized Residuals

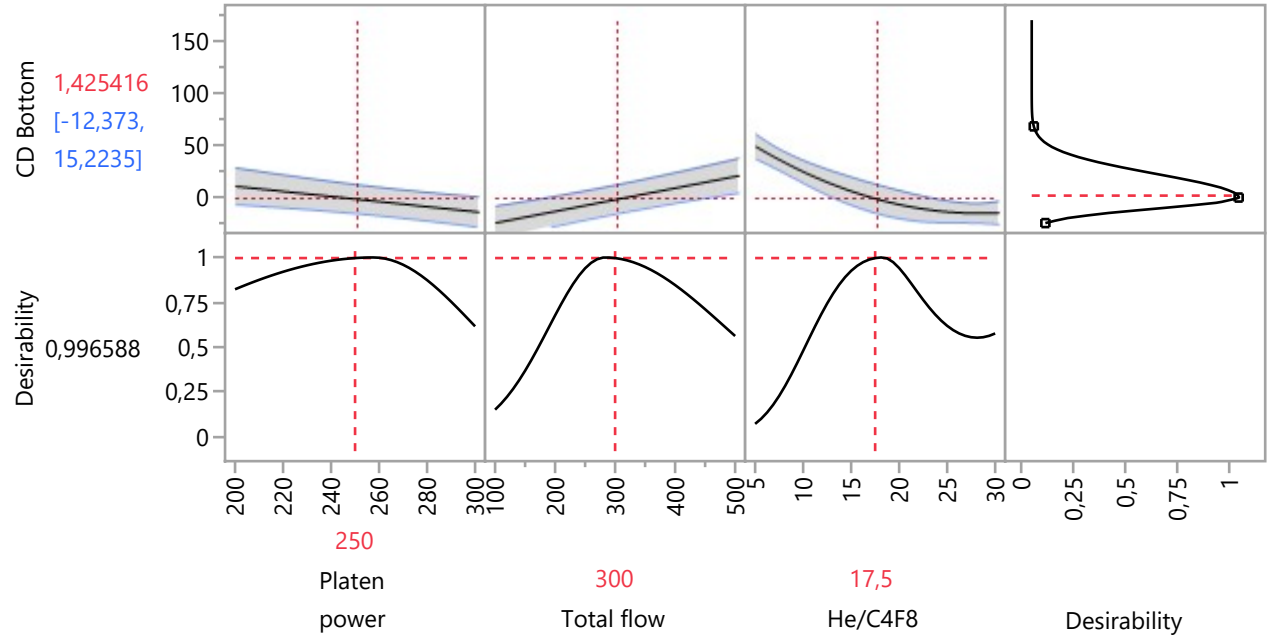


Externally studentized residuals with 95% simultaneous limits (Bonferroni) in red, individual limits in green.

Fit Group

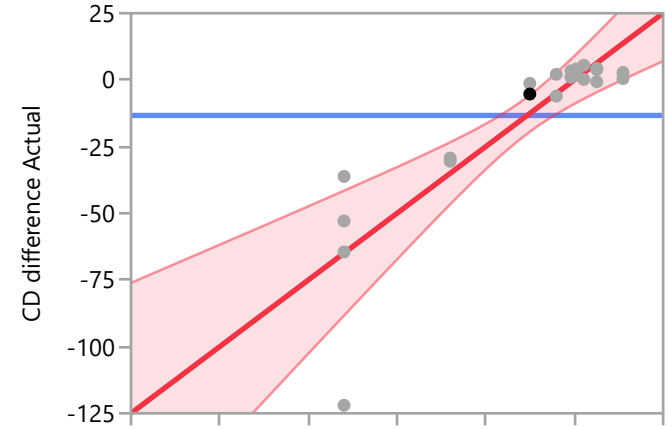
Response CD Bottom

Prediction Profiler



Response CD difference

Actual by Predicted Plot



Fit Group

Response CD difference

Actual by Predicted Plot

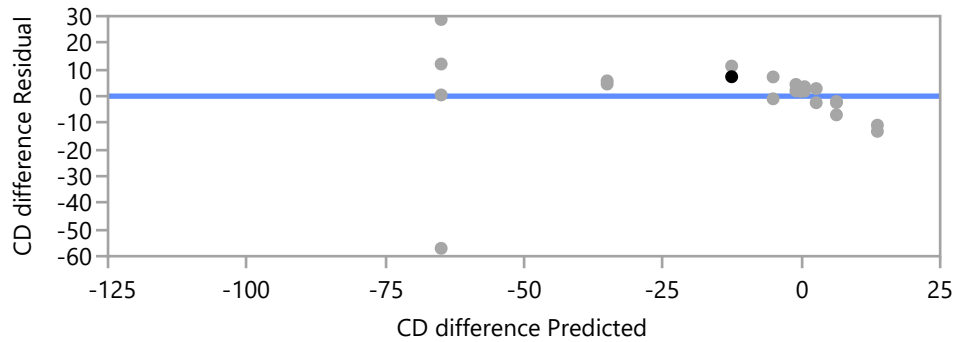
CD difference Predicted RMSE=16,108 RSq=0,76

PValue=<,0001

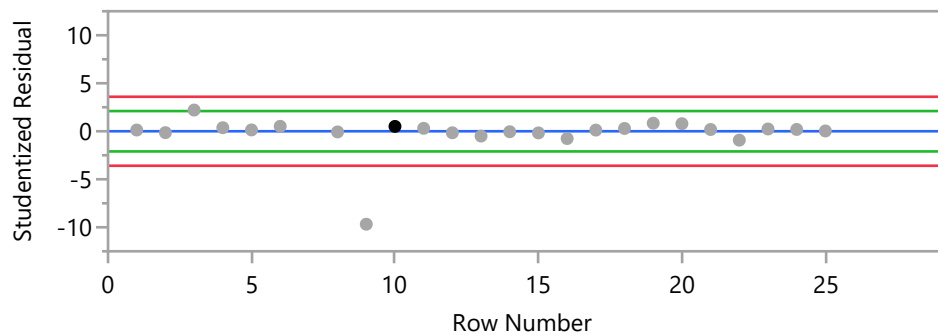
Effect Summary

Source	LogWorth	PValue
He/C4F8(5,30)	4,044	0,00009
Total flow*He/C4F8	2,871	0,00135
Total flow(100,500)	2,481	0,00330 ^
He/C4F8*He/C4F8	1,395	0,04026

Residual by Predicted Plot



Studentized Residuals



Externally studentized residuals with 95% simultaneous limits (Bonferroni) in red, individual limits in green.

Fit Group

Response CD difference

Prediction Profiler

